

## Structure of the As Vacancies on GaAs(110) Surfaces

S. B. Zhang and Alex Zunger

*National Renewable Energy Laboratory, Golden, Colorado 80401*

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We report a comprehensive study of the As vacancies ( $V_{As}$ ) in the GaAs(110) surface via *ab initio* total energy minimization. Previous scanning tunneling microscopy (STM) images of the  $V_{As}$  in *p*-type GaAs(110) were interpreted with a structure with outward movement of the Ga next to the vacancy. While our simulation of the STM images, using *ab initio* wave functions, agrees with experiment, our total energy minimization suggests, however, inward movement of Ga. We explain this apparent conflict as a charge induced band bending effect. As a consequence, we predicted that the STM images will depend on the applied bias voltage. We show that the atomic geometry of the surface  $V_{As}$  depends critically on the charge state  $q$  in sharp contrast with *bulk* vacancy. [S0031-9007(96)00556-X]

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The electronic and atomic structures of point defects on surfaces could differ significantly from their bulk counterparts. For *bulk* As vacancy  $V_{As}$

TABLE I. Direction of atomic displacements ( $\uparrow$  - outward,  $\downarrow$  - inward,  $\leftrightarrow$  - little displacement) near an As vacancy in GaAs(110). TB and PS stand for tight-binding and pseudopotential total energy calculations

Site	From total energy minimization			From STM images	
	TB (Ref. [2])	PS (Ref. [3])	PS (Present)	Expt. (Ref. [2])	Calc. (Present)
As	?	?	$\leftrightarrow$	$\downarrow$	$\downarrow$
Ga	$\uparrow$ $\approx 0.7$ Åd	$\downarrow$ $\leq 0.4$ Åd	$\downarrow$ $\approx 0.3$ Åd	$\uparrow$ $\approx 0.7$ Åd	$\uparrow$ $\approx 0.6$ Åd <sup>a</sup>

<sup>a</sup>Inferred from the calculated displacement  $\approx 0.4$  Åd with respect to the third nearest Ga atom and the measured [2] displacement of the third nearest Ga and Ga distance away  $\approx 0.2$  Åd.

$\epsilon_{\text{VBM}}$ ). The last term in Eq. (1) accounts for the energy of the  $n$  electrons or holes in the reservoir. Assuming that  $L_i$  is the supercell's  $i$ th dimension where  $i = x, y,$  and  $z$  ( $z$  is normal to the surface) and that  $\Delta z = z_2 - z_1 \ll L_z$  can be any interior, bulklike region of the GaAs slab,  $\epsilon_{\text{VBM}}$ , in principle, can be determined [1] by aligning the average potential

$$\bar{V} = \frac{1}{L_x L_y}$$

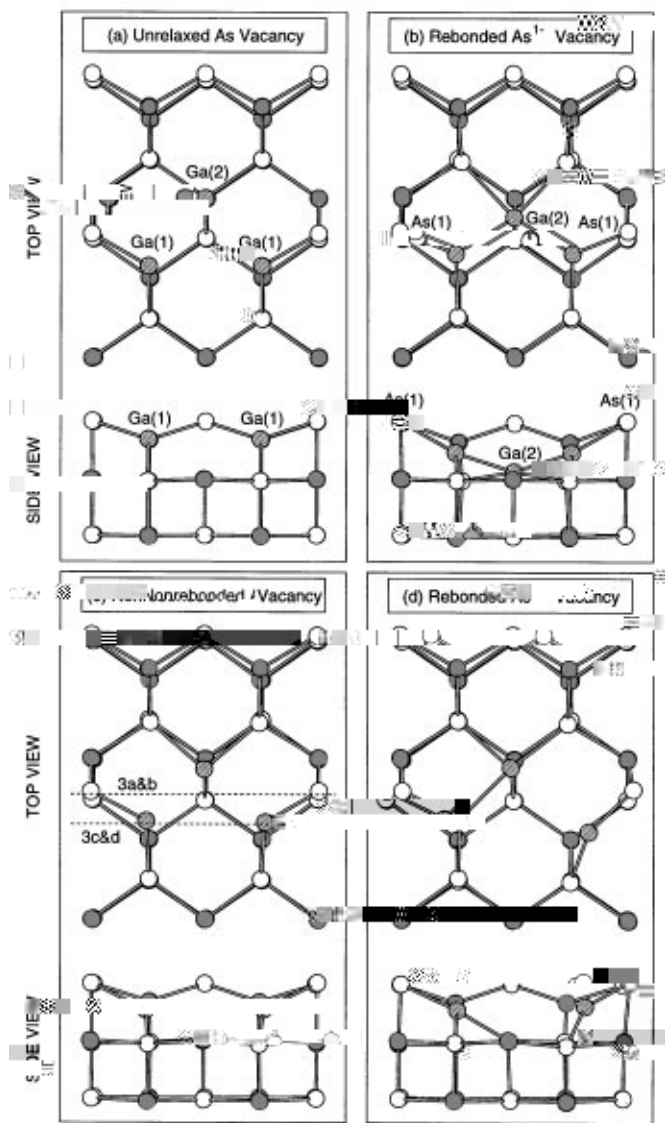


FIG. 1. Top and side views of the relaxed GaAs(110) surface

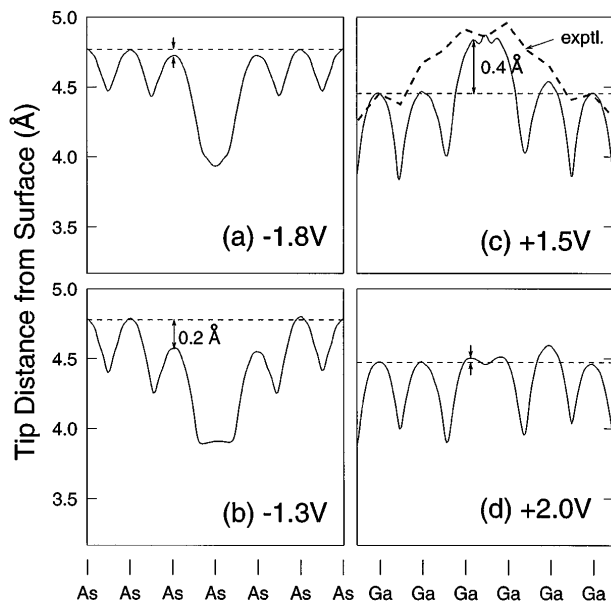


FIG. 3. Cross sections [see Fig. 1(c)] of the calculated 3D STM images at various biases for the nonrebonded  $V_{As}^{1+}$  center. The experimental data in (c) are taken from Ref. [2] and are aligned with the calculated results at the third nearest neighbor